

Substitute for form 1449/PTO (Revised 04/2003) INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)				Complete if Known	
				Application Number	
				Filing Date	
				First Named Inventor	
				Group Art Unit	
				Concurrently Herewith	
				Oghara et al.	
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				Examiner Name	
				Surdar	
				Attorney Docket Number	
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U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.	Document Number Number - Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages of Relevant Figures Appear

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code - Number Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	English Language Translation Attached
AKS	1	JP 2000-44875	02/15/2000		English Abstract	
	2	JP 9-194298	07/29/1997		English Abstract	
	3	JP 2001-130911	05/15/2001		English Abstract	
	4	JP 2001-115029	04/24/2001		English Abstract	
AKS	5	JP 2001-203197	07/27/2001		English Abstract	

OTHER DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	English Language Translation Attached
AKS	6	Inagaki et al., "Synthesis of Highly Ordered Mesoporous Materials from a Layered Polysilicate," <u>J. Chem. Soc., Chem. Commun.</u> , pp. 680-682, 1993	

CLT01/4638707v1

Examiner Signature	Asok Kumar Surdar	Date Considered	11/14/05
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*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609.
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